

In re. MORALES

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Attorney Docket No. SD-8214



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**CERTIFICATION UNDER 37 CFR 1.8**

I hereby certify that this New Application Transmittal and the documents referred to as enclosed therein are being deposited with the U. S. Postal Service on the **FEBRUARY 7, 2002**, addressed to the: Assistant Commissioner for Patents, Washington, D.C. 20231.

Date of Deposit: 2/7/02

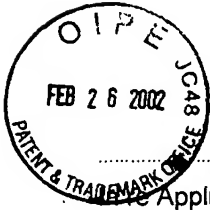
Maria F. Matos

Person Making Deposit

Maria F. Matos  
Signature

In re. MORALES

Attorney Docket No. SD-8214



IN THE U.S. PATENT AND TRADEMARK OFFICE

# 2  
8-22-02

Application of: MORALES, et al. )

Serial Number: not assigned )

Examiner: not assigned

Filed: 02/05/02 )

Group Art Unit: not assigned

For: SILICON MICRO-MOLD AND )

METHOD FOR FABRICATION )

Attorney Docket Number: SD-8214 )

Assistant Commissioner for Patents  
Washington, D. C. 20231

Date: 02/07/02

**INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR §1.97**

Sir:

Listed below on the attached Form PTO-1449 is information known to the Applicants. A copy of each of the listed publications is submitted herewith pursuant to 37 CFR §§1.97 and 1.98.

Applicant respectfully requests that the listed information be considered by the Examiner and be made of record in the above-identified application. Examiner is further requested to initial and return attached Form PTO-1449 in accordance with MPEP §609.

This statement is NOT intended to represent that a search has been made or that the information cited in the statement is, or is considered to be, material to patentability as defined in §1.56.

[ X ] This statement is filed under 37 CFR §1.97, subsection (b) because the submission was filed:

[ X ] within three months of the filing date of the application; OR

[ ] before the mailing date of the first Official Action on the merits, whichever comes last.

[ ] This statement is filed under 37 CFR §1.97, subsection (c), because the submission was made AFTER the latest of (1) three months beyond the filing date of a national application; (2) three months beyond the date of entry of the national stage as set forth in

§1.491 in an international application; OR (3) the mailing date of a first Official Action on the merits, but before the mailing date of the earlier of a final Official Action under §1.113 or a Notice of Allowability under §1.311. This statement is, therefore, accompanied by :

- ☐ a certification under §1.97(e); and
- ☐ the fee required under 37 CFR §1.17(p). The Commissioner is hereby authorized to charge Deposit Account No. 50-0583 in the amount of \$240.00, or the amount which is currently applicable. A duplicate copy of this paper is attached.

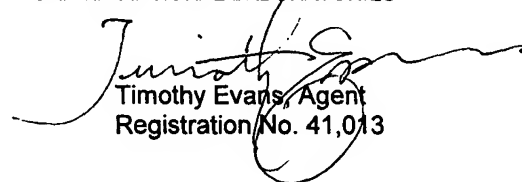
☐ This statement is filed under 37 CFR §1.97, subsection (d), because the submission was made AFTER the mailing date of the Final Action §1.113 or a Notice of Allowability under §1.311 but BEFORE payment of the Issue Fee. This statement is, therefore, accompanied by :

- ☐ a certification as specified under §1.97(e); AND
- ☐ a petition under §1.97(d) requesting consideration of this statement; AND
- ☐ the fee required under 37 CFR §1.17(i)(1). The Commissioner is hereby authorized to charge Depository Account No. 50-0583 in the amount of \$130.00, or the amount which is currently applicable . A duplicate copy of this paper is attached.

☒ The Commissioner is hereby authorized to charge to Deposit Account No. 50-0583 any fee, any underpayment of additional fees, or credit any overpayment associated with this communication, and which has have been inadvertently overlooked.

Respectfully submitted,

SANDIA NATIONAL LABORATORIES

  
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Attachments:

PTO/Form 1449 (Modified)  
Copies of referenced citations  
Return Receipt Postcard

Form PTO-1449 (SNL-Modified) (2-91)	Atty D ck t No: SD-8214
List of Patents and Publications for Applicant's	S rial Number: n t assigned
Information Disclosure Statement	Applicant: MORALES
(use several sheets if necessary)	FILING DATE: 02/05/02

REFERENCE DESIGNATION

Ex'r	U.S. Patent Documents			Sub
Init	Document No.	Date	Name	Class   Class   File Date (when applicable)

IAA  
IAB

Ex'r	Foreign Patent Documents			Sub	Translation?
Init	Document No.	Date	Name	Class   Class	Yes   No

IAB CN 1262460 8/9/00 CHEN, et al. G03F007-00 X

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

ICA ✓ BECKER, E.W.; EHRFELD, W.; HAGMANN, P.; MANER, A.; MUENCHMEYER, D.; "Fabrication of microstructures with high aspect ratios and great structural heights by synchrotron radiation lithography, galvanofarming, and plastic moulding (LIGA process)," *Microelectronic Engineering*, vol. 4 (1986) pp. 35 – 56 Published by Elsevier Scientific Publishers B.V.

ICB ✓ EHRFELD, W.; GLASHAUSER, W.; MUENCHMEYER, D.; SCHELB, W.; "Mask making for synchrotron radiation light," *Microelectronic Engineering*, vol. 5 (1986) pp. 463 – 470 Published by Elsevier Scientific Publishers B.V.

ICC ✓ EHRFELD, W.; LEHR, H.; "Deep x-ray lithography for the production of three-dimensional microstructures from metals, polymers, and ceramics," *Radiat. Phys. Chem.*, vol. 45 No. 3 (1995) pp. 349 – 365 Published by Pergamon Press, Elsevier Scientific Ltd.

ICD ✓ BHARDWAJ, J.K.; ASHRAF, H.; "Advanced silicon etching using high density plasmas" *Proceedings of SPIE* vol. 2639 (1996) pp. 224 – 233 Published by SPIE – The International Society for Optical Engineering

ICE ✓ AJMERA, P.K.; STADLER, S.; ABDOLLAHI, N.; "Development of a low –cost X-ray mask for high-aspect ratio MEM smart structures" *Proceedings of SPIE* vol. 3328 (1998) pp. 14 – 22 Published by SPIE – The International Society for Optical Engineering

ICF ✓ SHEW, B.-Y.; CHENG, Y.; SHIH, W.-P.; LU, M.; LEE, W.H.; "High precision, low cost mask for deep x-ray lithography" *Microsystems Technology*, vol. 4 (1998) pp. 66 – 69 Published by Springer – Verlag

ICH ✓ KLEIN, J.; GUCKEL, D.P.; SIDDONS, D.J.; JOHNSON, E.D.; "X-ray masks for very deep X-rGy lithography" *Microsystems Technology*, vol. 4 (1998) pp. 70 – 73 Published by Springer – Verlag

ICH ✓ SHEU, J.T.; CHIANG, S.; SU, S.; "Fabrication of intermediate mask for deep x-ray lithography" *Microsystems Technology*, vol. 4 (1998) pp. 74 – 76 Published by Springer – Verlag

Examiner:	Date Considered:
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[CI] ✓ CHEN, D.; ZHANG, D.; DING, G.; ZHAO, X.; ZHANG, J.; YANG, C.; CAI, B.; "DEM technique: A new three-dimensional micro fabrication technique for non-silicon materials" *Proceedings of SPIE* vol. 3680 No. 2 (1999) pp. 1099 – 1104 Published by SPIE – The International Society for Optical Engineering

[CJ] ✓ HARRIS, C.; DESTA, Y.; KELLY, K.W.; CALDERON, G.; "Inexpensive, quickly producible X-ray mask for LIGA" *Microsystems Technology*, vol. 5 (1999) pp. 189 – 195 Published by Springer – Verlag

[CK] ✓ COANE, P.; GIASOLLI, R.; LEDGER, S.; LAIN, K.; LING, Z.; GOETTERT, J.; "Fabrication of HARM structures by deep X-ray lithography using graphite mask technology" *Microsystems Technology*, vol. 6 (2000) pp. 94 – 98 Published by Springer – Verlag

[CL] ✓ CHEN, D.; LEI, W.; WANG, C.; LI, C.; GUO, X.; MAO, H.; ZHANG, D.; YI, F.; "New type of X-ray mask fabricated using inductively coupled plasma deepetching" *Microsystems Technology*, vol. 7 (2001) pp. 71 – 74 Published by Springer – Verlag

Examiner:

Date Considered: